



Recent developments at HLL, including new LGAD silicon sensors

Jelena Ninković for MPG HLL Team

● MPS Semiconductor Laboratory (in German: MPG Halbleiterlabor - HLL)

Central facility of the Max Planck Society
with 40 employees: scientists, engineers and technicians + guest scientists, engineers and students

At present @ Siemens Campus Neuperlach Munich



- 1000m² of clean room area
- 330m² of ISO3 area
- Full 6 inch silicon process line

From end 2023 @ IPP Campus Garching



- 1500m² of clean room area
- 600m² of ISO3 & ISO4 area
- 8 inch silicon process line

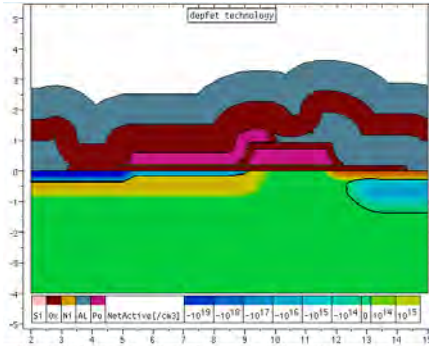


From 2024 HLL will be part of
Munich Quantum Valley

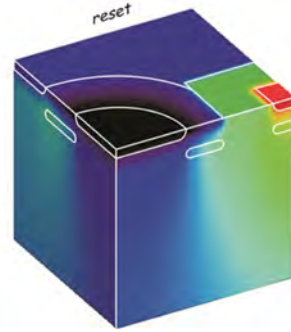
MPG HLL is developing and producing fully depleted silicon radiation sensors
with integrated electronics optimized for different scientific projects

● Inside HLL – Sensors and Systems : Design, fabrication & Test

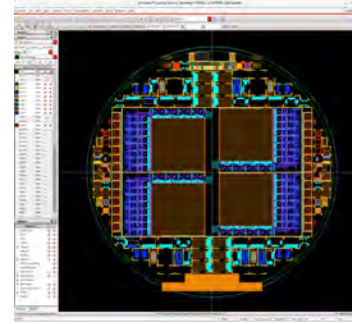
Process simulation



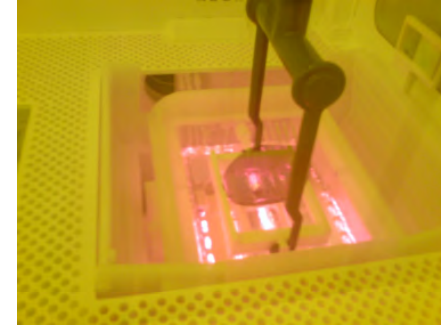
Device simulation, 2D and 3D



State-of-the-art layout tools



In house fabrication



Wire bonding, hybrid assembly



@ HLL:

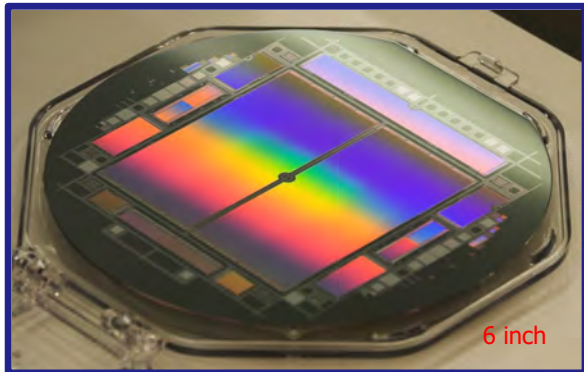
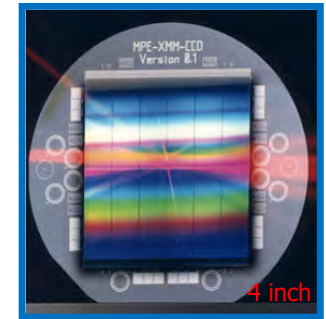
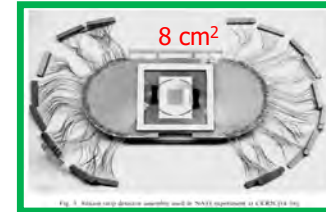
- sensor design and fabrication
- interconnection
- system/camera design and test

System test facilities



● Highlights from the past

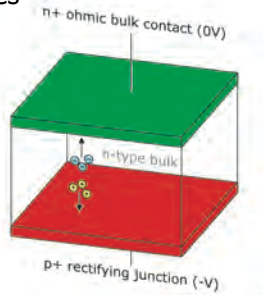
- **NA11 - NA32 experiments at CERN (1982 -1988) [MPP]**
First usage of silicon strip detectors in the high energy physics
- **XMM Newton (launch 1999) [MPE]**
Large area device with 100% fill factor, and very sensitive entrance window
- **ATLAS (2004) [MPP]**
development at HLL, fabrication at industry, 3.000 wafers produced
- **LAMP (2011 – 2014) [CFEL]**
Photon science: Large area device with ultra sensitive entrance windows



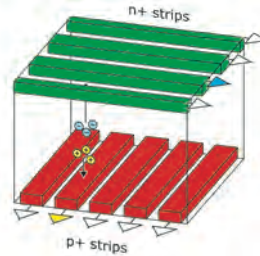
● Devices @ HLL

● Building blocks

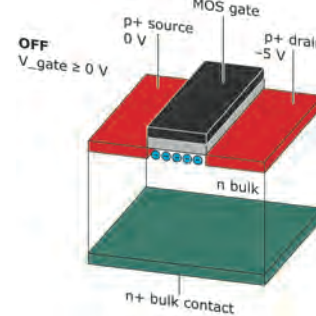
Diodes



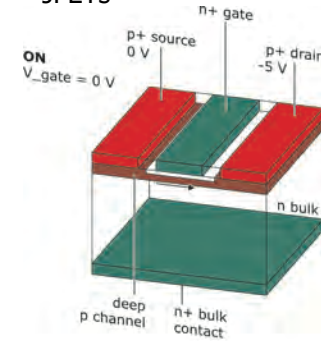
Strip detectors



MOSFETs

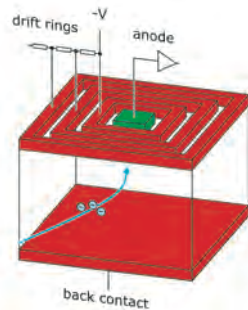


JFETs

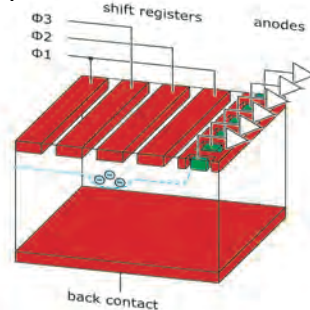


● Devices

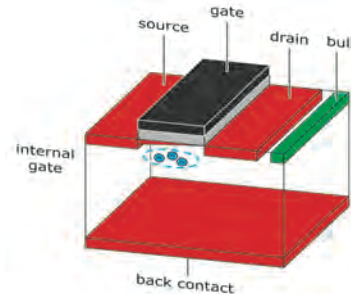
Silicon drift detectors (SDD)



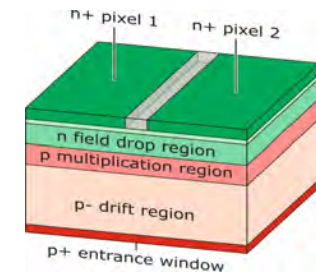
pnCCDs



DEPFETs

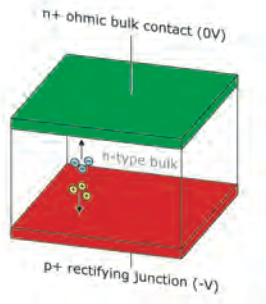


Avalanche devices

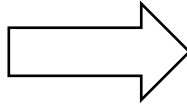


● Advanced detector concepts

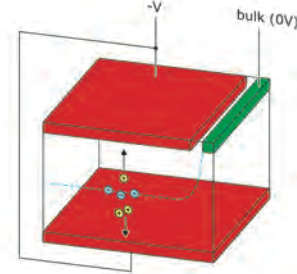
Diode



Sideward depletion structure
Emilio Gatti & Pavel Rehak, 1983

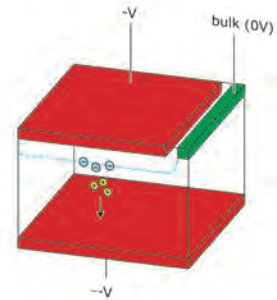


Symmetric bias



and

Asymmetric bias



▷ electronic noise

$$ENC = \sqrt{k \frac{2kT}{g_m} C_{tot}^2 A_1 \frac{1}{l} + 2\check{K} a_r C_{tot}^2 A_2 + q I_L A_3 l}$$

▷ optimum shaping time

$$l_{opt} = \sqrt{\frac{2A_3}{A_1} \frac{kT}{q} \frac{C_{tot}^2}{I_L} \frac{2}{3g_m}}$$

↳ for **good energy resolution and high count rate capability**

the total capacitance must be minimized!!

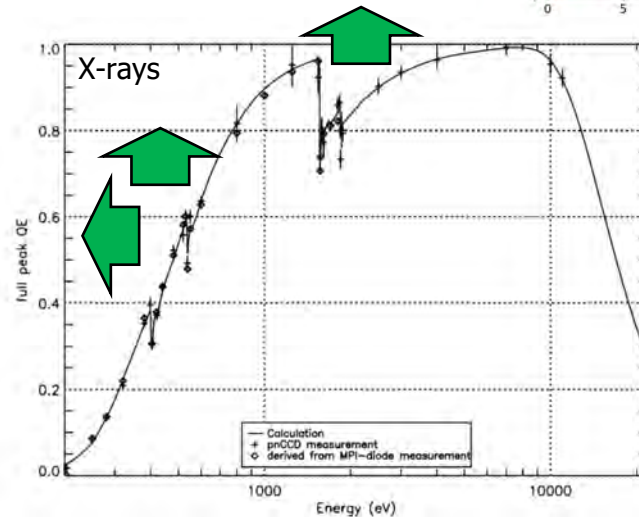
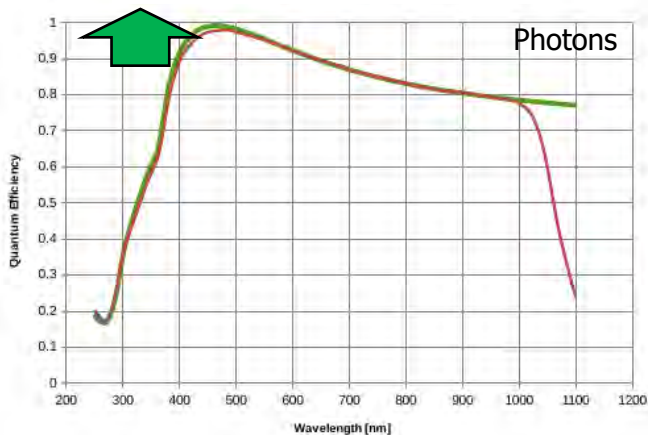
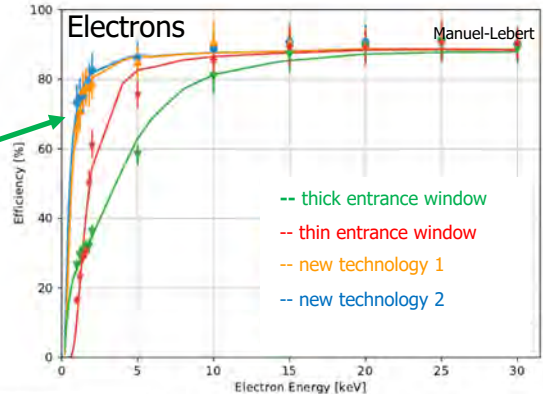
- ▷ volume is fully depleted by reverse biased diodes on both surfaces
- ▷ minimum capacitance of bulk contact, independent of overall area
- ▷ potential minimum for majority carriers (electrons @ n-Si)

● Entrance window engineering – application optimization

• anti-reflective coating (ARC)

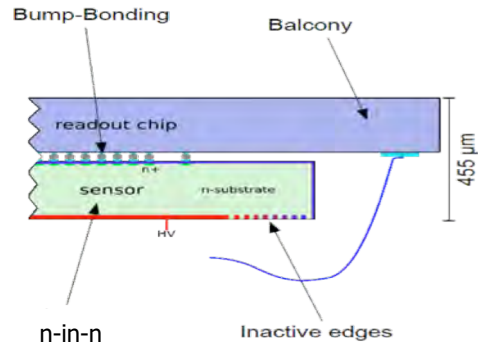
- ▷ sequence of dielectric layers deposited on the entrance window
- ▷ variation of material and thickness
- ▷ transmittance tuning to application needs
- ▷ blocking filters
- ▷ mechanical protection
- ▷ optical coupling

Ongoing developments
Reduction of dead layer to < 20nm

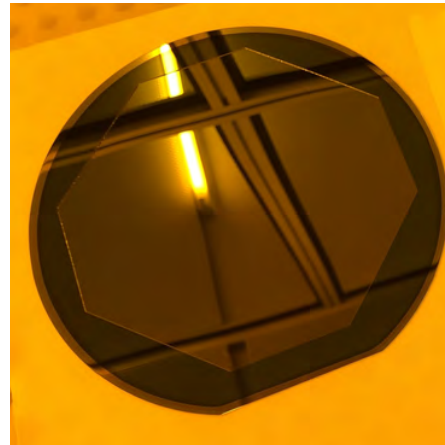
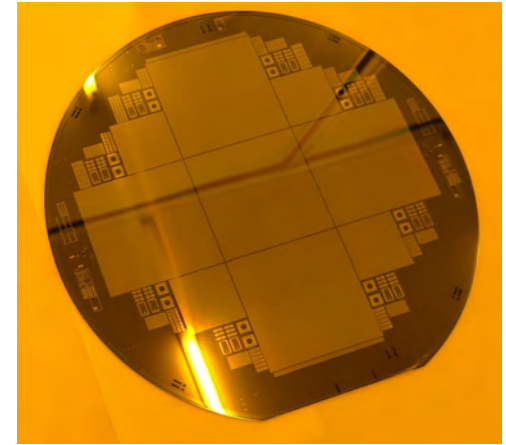


● PAD detectors for ATLAS

Thin planar sensors for high luminosity upgrade of ATLAS experiment
→ Collaboration partner Max Planck for Physics



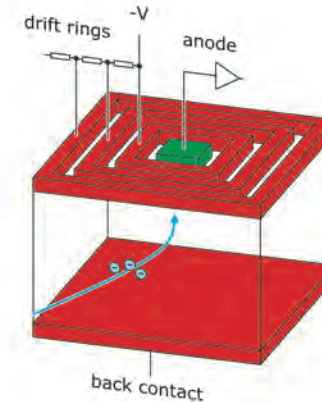
- 100 μm thin sensors
- 50x50 μm^2 pixels



● Advanced detector concepts – Silicon drift detector

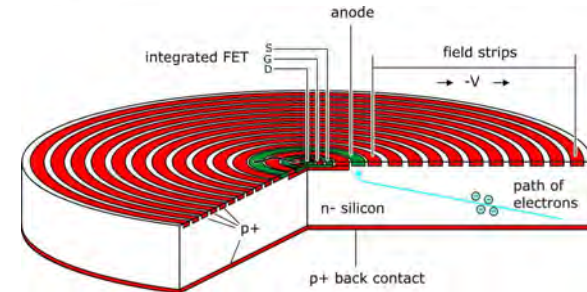
spectroscopy SDD - Josef Kemmer & Gerhard Lutz, 1987
one-sided field strip system

- ▷ non-structured backside diode
 - ↳ optimized for photon spectroscopy
 - ↳ irradiation through homogeneous thin entrance window



SDD with on-chip FET - Peter Lechner et al., 1994
backside illuminated

- ▷ integration of 1st amplifying FET
 - ↳ minimization of total capacitance
 - ↳ good energy resolution
 - ↳ high count rate capability
 - ↳ robust against pickup, microphony



- pin diode $10 \text{ mm}^2 \times 300 \text{ }\mu\text{m}$ $C_{\text{tot}} = 3.5 \text{ pF}$
- SDD with FET 10 mm^2 $C_{\text{tot}} = 150 \text{ fF}$

- ▷ Application: X-ray spectroscopy (XRF, EDX)
 γ -ray imaging (scintillator readout)

● SDD highlights

Mini SDD - DSSC @ EuXFEL (imaging of X-ray diffraction patterns)



M. Porro et al., *The MiniSDD-based 1-Megapixel Camera of the DSSC Project for the European XFEL*, IEEE TNS 68(6), pp. 1334 - 1350, June 2021

camera	1024 x 1024 pixels 21 x 21 cm ² 32 sensor chips 4 quadrants central hole for direct beam
sensor	mini-SDD cells 128 x 256 pixels 3.0 x 6.2 cm ² (chip)
hex. pixel pitch	204 μm × 236 μm
energy range	0.25 keV – 6 keV
noise	60 el. r.m.s.
peak frame rate	4.5 MHz
frame storage	800 frames

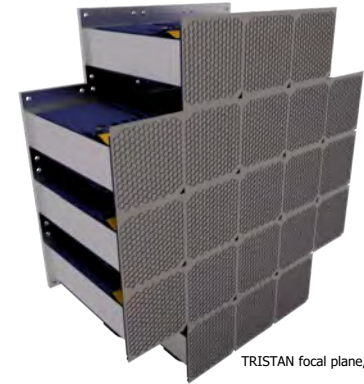
eXTP (enhanced X-ray Timing and Polarimetry) SFA (spectroscopic focusing array) (fast time-resolved X-ray spectroscopy)



SDD layout plot

SFA instrument	11 telescopes & sensors sensors out of focus
sensor	19-cells SDD
SDD cell	hexagonal 3.2 mm side length 30 mm² area
energy resolution	< 180 eV (FWHM @ 6 keV)
time resolution	< 10 μsec

TRISTAN (tritium sterile anti-neutrino) @ KIT sterile neutrino search by electron spectroscopy



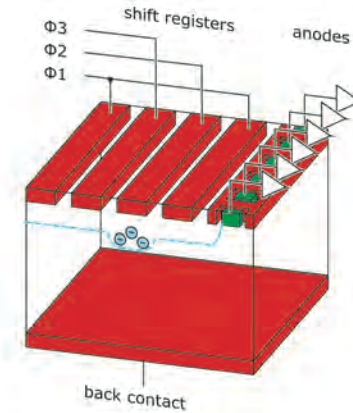
TRISTAN focal plane, 21 modules.

system	21 sensors 20 cm diameter
sensor	SDD with integrated FET 166 cells (~ 14 x 12 array) 3.8 x 4.0 cm² (chip)
SDD cell	hexagonal, 3 mm side length 7 mm ² area
energy resolution	< 300 eV FWHM @ 20 keV
count rate	≤ 10 ⁸ /sec on focal plane ≤ 10 ⁵ /sec on sensor cell
dead layer	as thin as possible

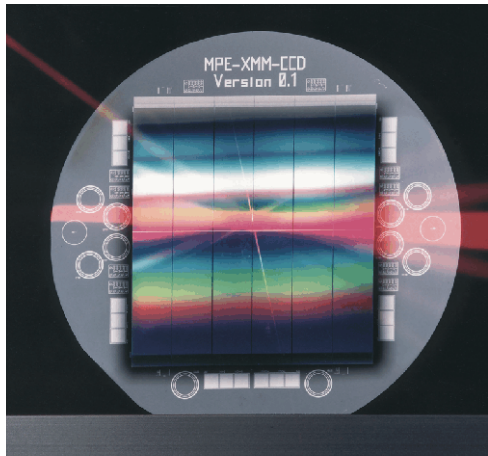
● Advanced detector concepts - pnCCD

pnCCD - Lothar Strüder et al., 1987

- ▷ definition of potential pockets by differently reverse-biased diodes
- ▷ charge transport by periodic clocking of shift registers
- ▷ column-parallel readout → high frame rate ($\sim 4 \mu\text{s}$ / row)
- ▷ integrated 1st FET (1 / column) → low noise ($< 2\text{el. ENC}$)
- ▷ backside illuminated, fully depleted → high quantum efficiency



- ▷ applications
 - X-ray imaging & spectroscopy
 - optical light imaging



pn-CCD for XMM-Newton (since 1999 in space)

- produced at MPG HLL
- monolithic $6 \times 6 \text{ cm}^2$
- pixel size $150 \times 150 \mu\text{m}^2$
- format 384×400 pixel

- World leading soft X-ray large area pnCCD devices @ MPG HLL

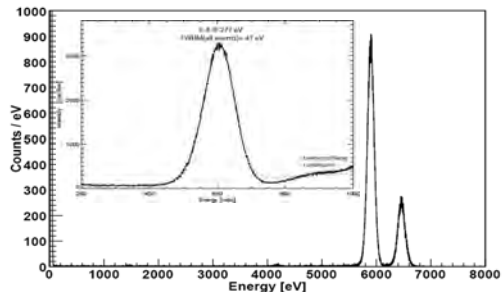
eROSITA

X-ray imaging & spectroscopy



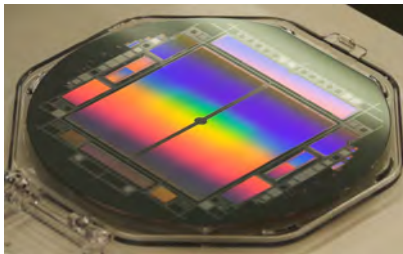
Sensor: $3 \times 3 \text{ cm}^2$
 384×384

Pixel size: $75 \times 75 \mu\text{m}^2$
Frame time: 50msec (20Hz)



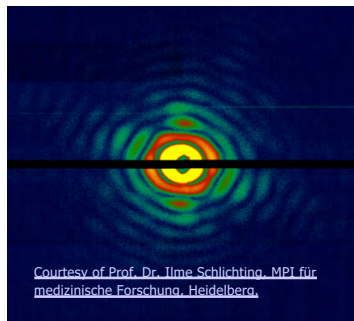
CAMP / LAMP

Soft X-ray camera for Photon science



Sensor: $3.7 \times 7.8 \text{ cm}^2$
 1024×512 pixels.

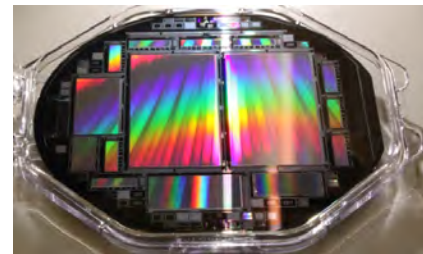
Pixel size: $75 \times 75 \mu\text{m}^2$
Frame time: 8 msec (up to 120Hz)



Courtesy of Prof. Dr. Ilme Schlichting, MPI für
medizinische Forschung, Heidelberg.

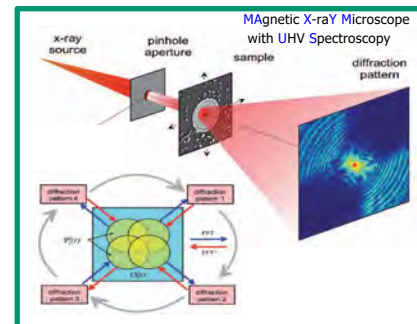
FSP – TNG for MAXIMUS

Fast Small Pixel – The Next Generation



Sensor: $3.7 \times 7.4 \text{ cm}^2$
 $1024 \times 1024 + (2 \times 512)$ pixels

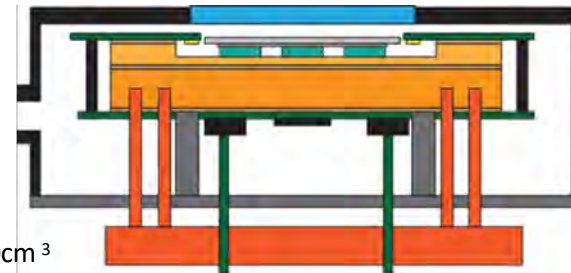
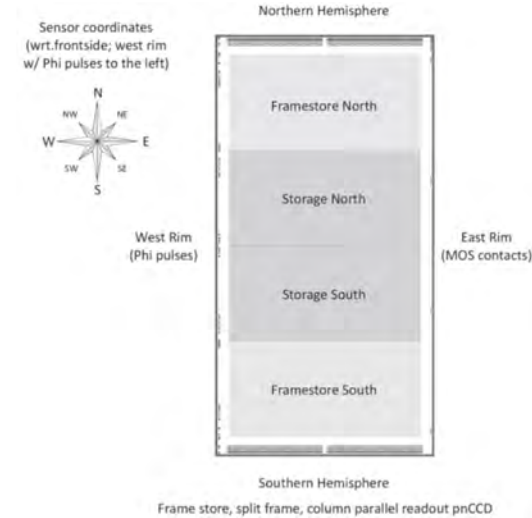
Pixel size: $36 \times 36 \mu\text{m}^2$
Frame time: 2.5 msec (400Hz)



● Fast Small Pixel pnCCDs (FSP) @ HLL

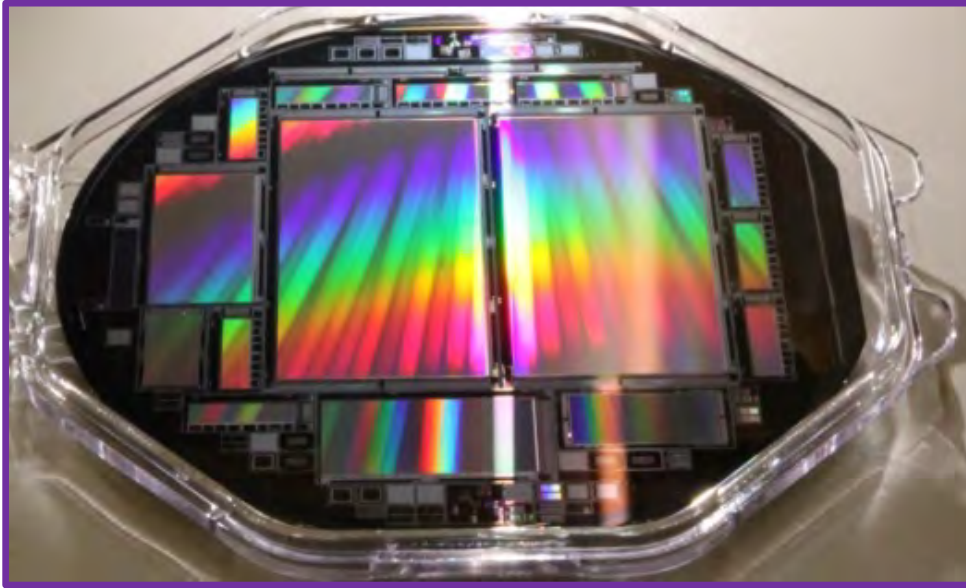
Device characteristics:

- pnCCD concept:
 - Backside illuminated,
 - frame store,
 - split frame,
 - column-parallel readout
- Format: **1k x 1k** storage, 2 x 1 k x 0.5 k framestore
- Pixel size: **36 x 36 μm^2**
- Total sensitive area: 36.8 x 73.3 mm²
- Total chip size: 4.2 x 8.1 cm²
- Operating temperature: -35°C (target)
- Target operating frame rate: **400 Hz** ($\sim 4 \mu\text{s}$ / row)
- Data rate: 840 Mbyte / s (16 bit)

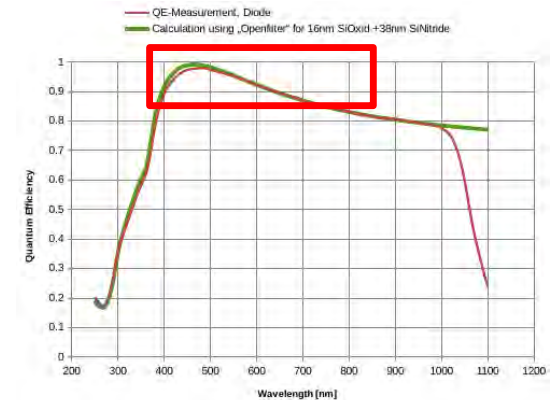


Compact vacuum-tight camera housing $\sim 18 \times 25 \times 10 \text{ cm}^3$

- FSP production



Optimized for two applications:
Soft X-rays and optical application

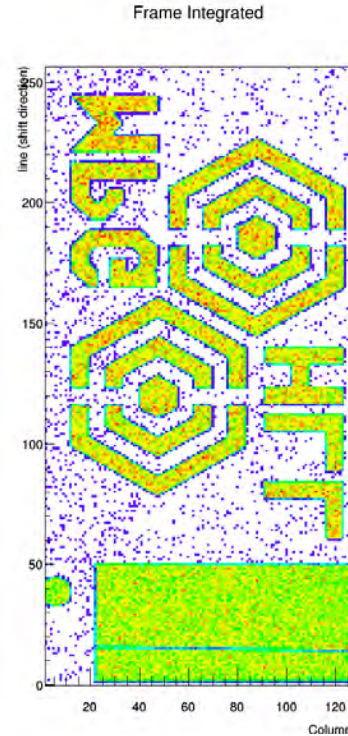


- X ray imaging using small pixel pnCCDs

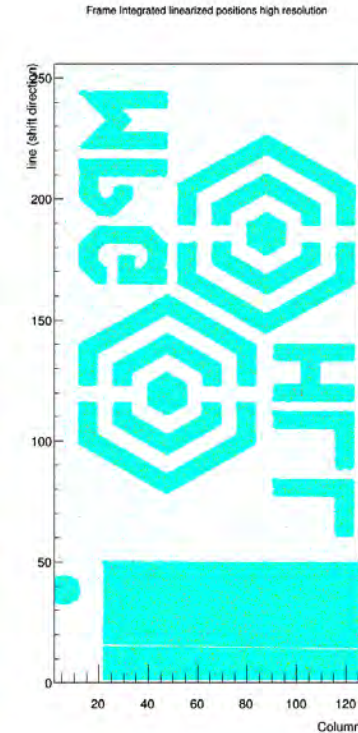
Imaging of a collimated Fe^{55} Source through a mask + goldwire



Mikroskopie Image of mask and wire in front of the pnCCD.

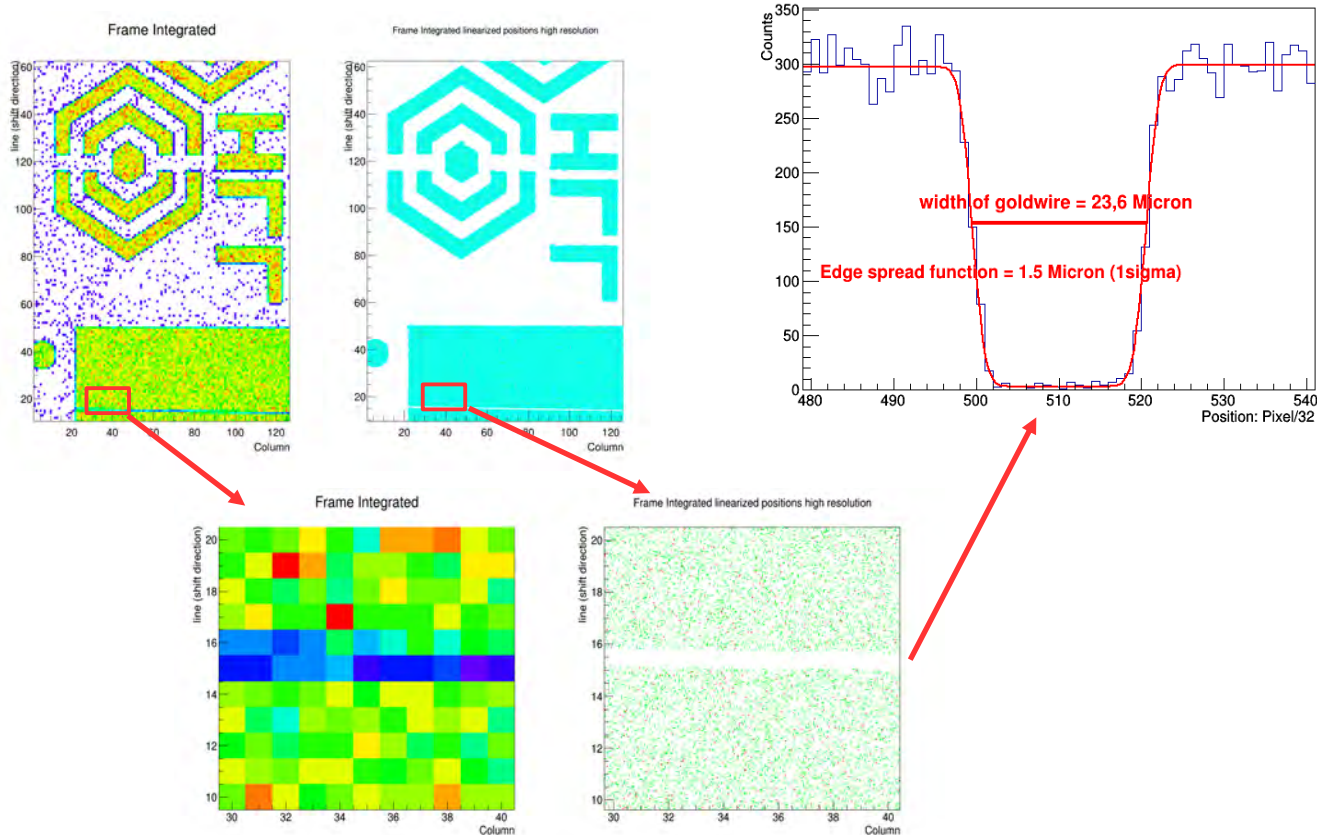


Frame as obtained by integrating Photons per pixel



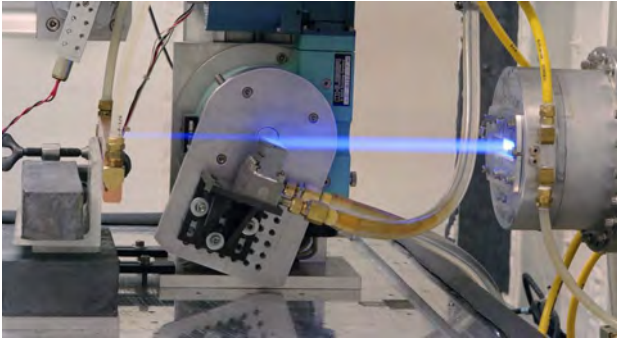
Frame as obtained by cluster reconstruction and integration per subpixel (32x32 subgrid)

● Image Resolution for Cluster Imaging @ 5.9 keV

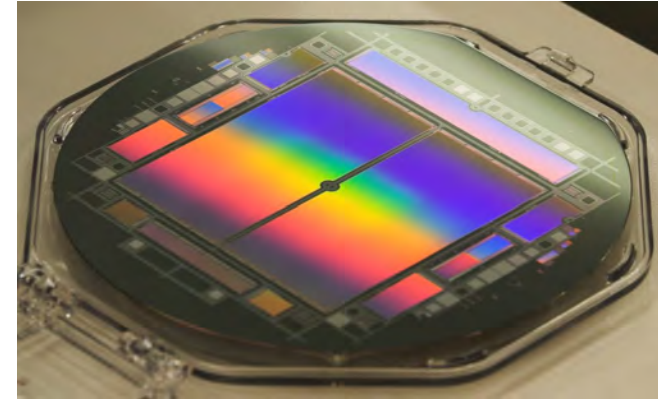


● FEL radiation detection

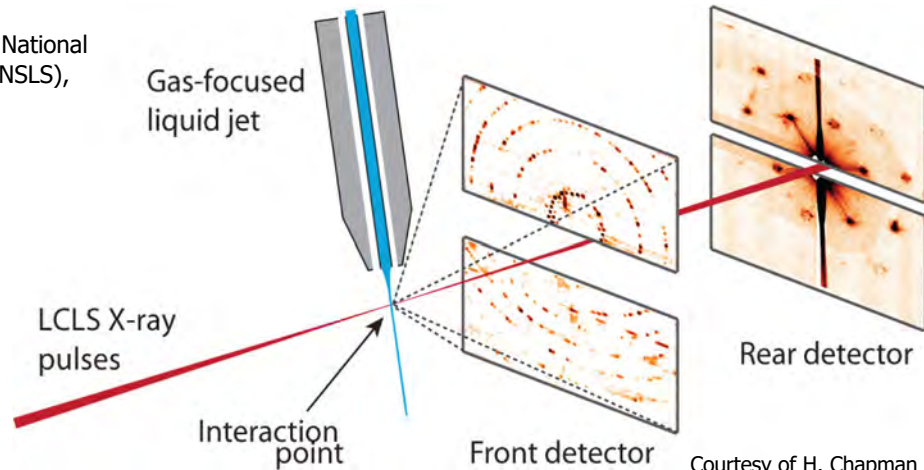
■ Sensors for LCLS (collaboration partner MP Extraterrestrial Physics)



Synchrotron light from the National Synchrotron Light Source (NSLS), Brookhaven

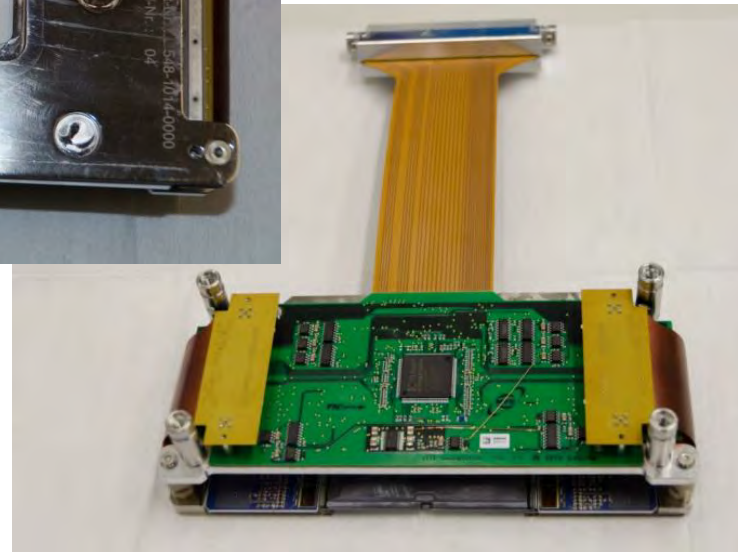
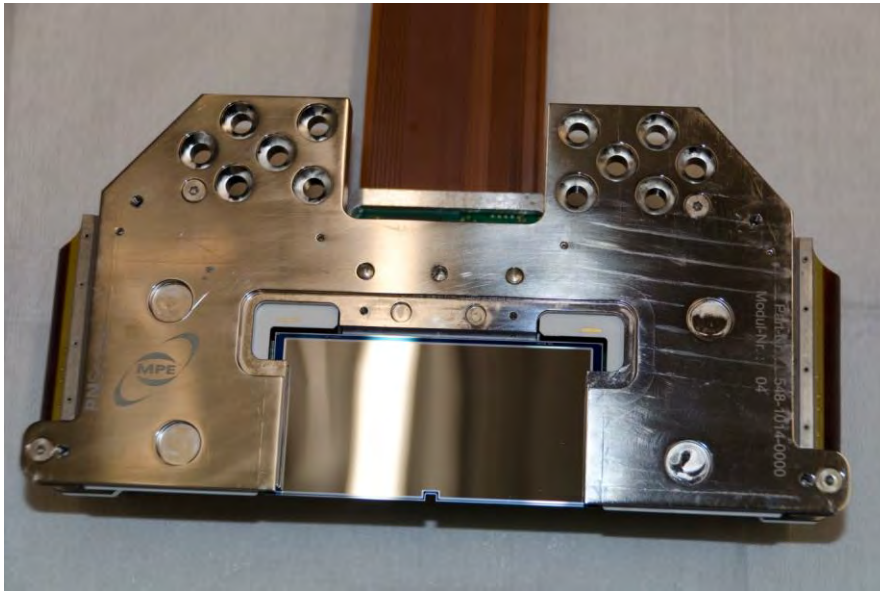


- ▷ Large area pnCCDs: 30 cm^2
- ▷ 1024×512 pixel of $75 \times 75 \text{ } \mu\text{m}^2$
- ▷ $3.7 \times 7.8 \text{ cm}^2$



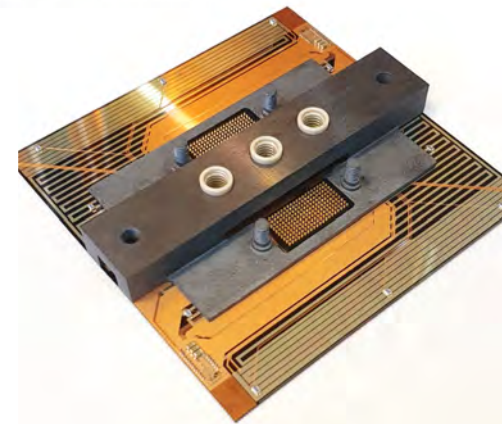
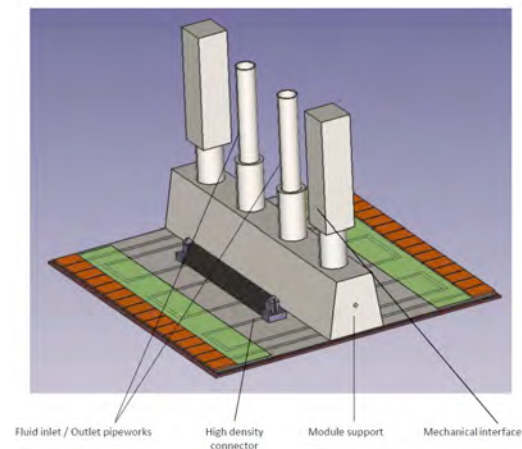
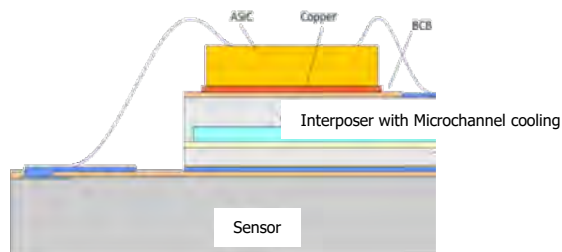
Courtesy of H. Chapman

- LAMP module



● In development - four side buttable pnCCDs

- no frame store
- Split frame, column parallel readout for optimized framerate
- $75 \times 75 \mu\text{m}^2$ pixels
- 1 MPixel array
- Sensitive area $76.8 \times 76.8 \text{ mm}^2$
- Narrow guard ring structure
- Chip size $77.65 \times 78.05 \text{ mm}^2$
- 2 times 1024 JFETs read simultaneously
- Readout with 2 x 16 VERITAS II ICs with 64 channels each



Goal:

More compact system design by improving the electronics integration density.

Lightweight mechanical design to reduce both thermal and inert mass.

Device independent platform.

Versatile use cases. - sensors to be 4-side buttable with minimum sensitivity gap

More compact sensor design minimal guard ring structure

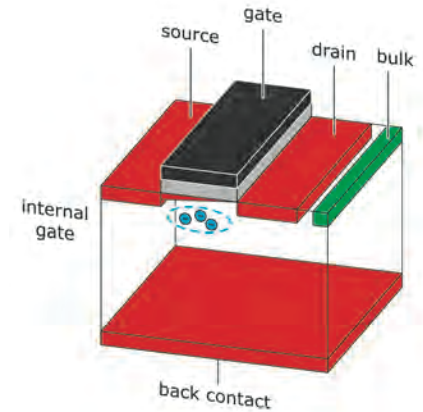
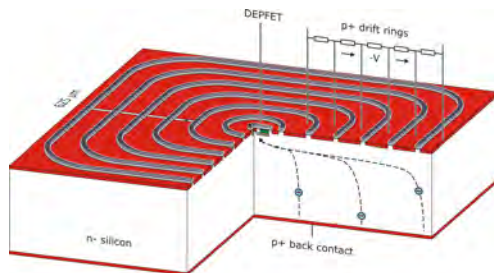
Standardized data I/O interfaces - high-performance FPGA based hardware as smart backend in the system.

Integrated housekeeping and diagnosis functions

● Advanced detector concepts

DEPFET - Josef Kemmer & Gerhard Lutz, 1987

- ▷ p-MOSFET on fully depleted n-substrate
- fully depleted sensitive volume
 - fast signal rise time (\sim ns), small cluster size
- Fabrication at MPG HLL
 - Wafer scale devices possible
 - no stitching, 100% fill factor
- Charge collection in "off" state, read out on demand
 - potentially low power device
 - Non destructive readout
- internal amplification
 - charge-to-current conversion (500 pA/el.)
 - large signal, even for thin devices
 - r/o cap. independent of sensor thickness (20 fF)

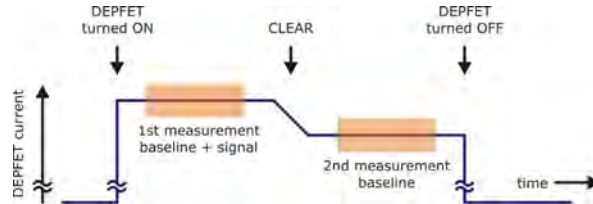


- ▷ applications
 - unit cell of active pixel sensor
 - ↳ X-ray imaging & spectroscopy
 - ↳ particle tracking
 - integrated readout device of SDD, CCD, ...
- ▷ format \sim cm² ... wafer scale
- ▷ thickness 25... 450 μ m
- ▷ pixel size 20 ... 150 μ m ... 1 cm² (DEPFET & SDD)
- ▷ readout time 90ns ... 4 μ sec / row
- ▷ low noise down to <2 el. ENC

● Advanced detector concepts

DEPFET readout

▷ readout sequence



➤ Double sampling

- 1st measurement: signal + baseline
- clear: removal of signal charges
- 2nd measurement: baseline
- difference = signal

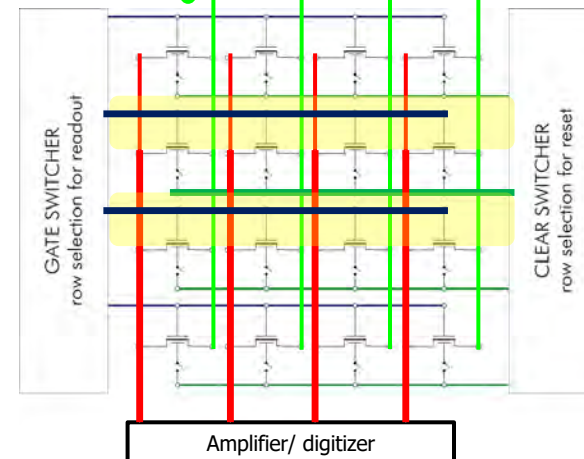
➤ Single sampling

- Measure pedestals and store
- Read once and clear

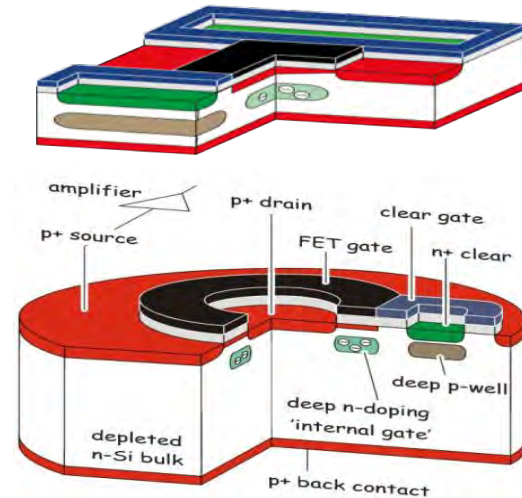
▷ active pixel sensor operation

- horizontal supply lines, row selection
- vertical signal lines
- 1 active row, other pixels integrating

Rolling shutter read out



● DEPFET classes

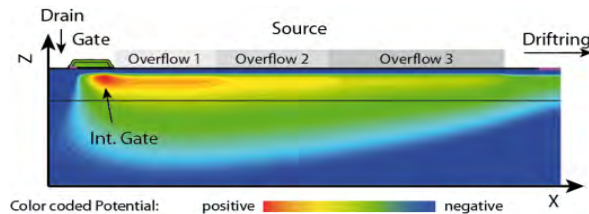


Thin & small pixel: vertex, low E electron detectors (TEM)

pixel size: $20\mu\text{m} \dots 75\mu\text{m}$
 read out time per row: 25ns-100ns
 Noise: ≈ 100 el ENC
 thin detectors: $50\mu\text{m} \dots 75\mu\text{m} \rightarrow$ still large signal: $40\text{nA}/\mu\text{m}$ for MIP

Low noise: Spectroscopic X-Ray imaging

pixel size: $100\mu\text{m}$, with drift rings several 100s of μm
 read out time per row: few μs
 Noise: ≈ 4 el ENC
 fully depleted, the thicker the better \rightarrow large QE for higher E



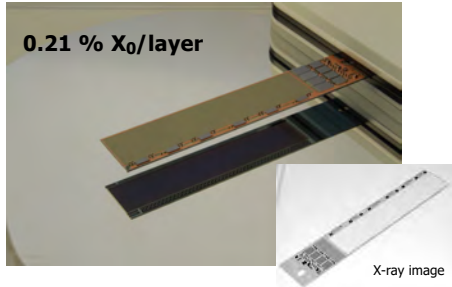
High Dynamic range

DEPFET Sensor with Signal Compression
 Sensitivity to single photons and high dynamic range
 pixel size: $60 - 200 \mu\text{m}$

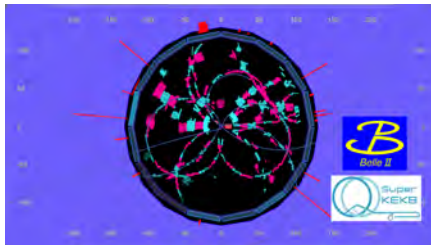
● Highlights from DEPFET projects

BELLE II pixel detector

High energy particle vertexing

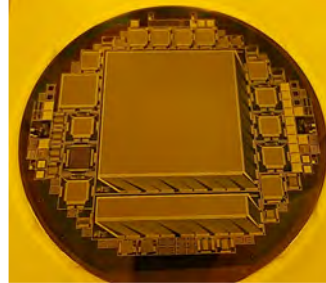


Active area 12.5 x 44.8(61.44)mm²
 250 x 800 pixels
 Thickness: **75 μ m**
 rolling shutter mode
 Pixel size: 50 x 55(85) μ m²
 Frame time: 20ms (50kHz) (10MHz -row)

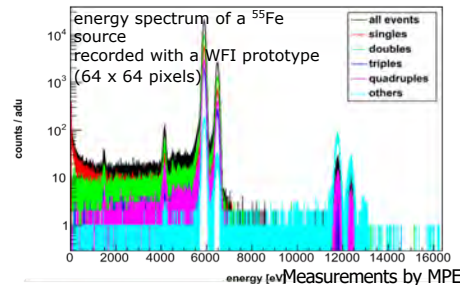


ATHENA Wide Field Imager

the **A**dvanced **T**elescope for **H**igh-**E**nergy **A**strophysics
as ESA's next-generation X-ray astronomy observatory

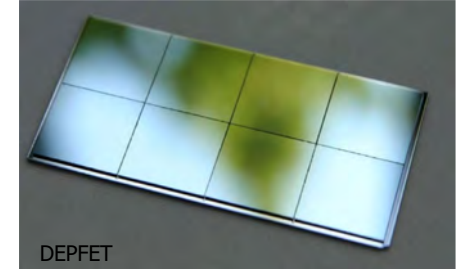


Sensor: 512 x 512 pixels
 78.00 x 76.15 mm²
 rolling shutter mode
 Pixel size: 130x 130 μ m²
 Frame time: **1.28 msec, i.e. 2.5 μ sec / row**
 with 128 eV (singles) & 136 eV (all)

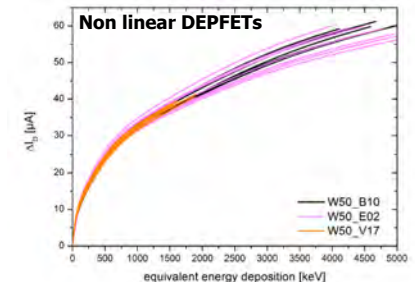


DSSC @ EuXFEL

DEPFET Sensor with **S**ignal **C**ompression
(imaging of X-ray diffraction patterns)

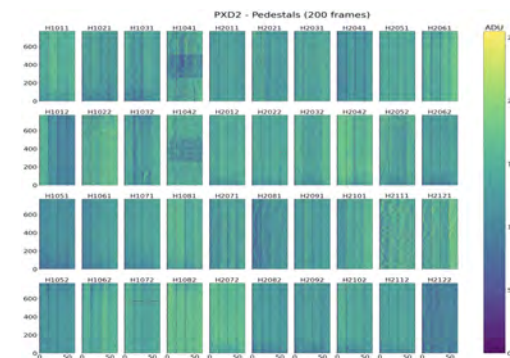
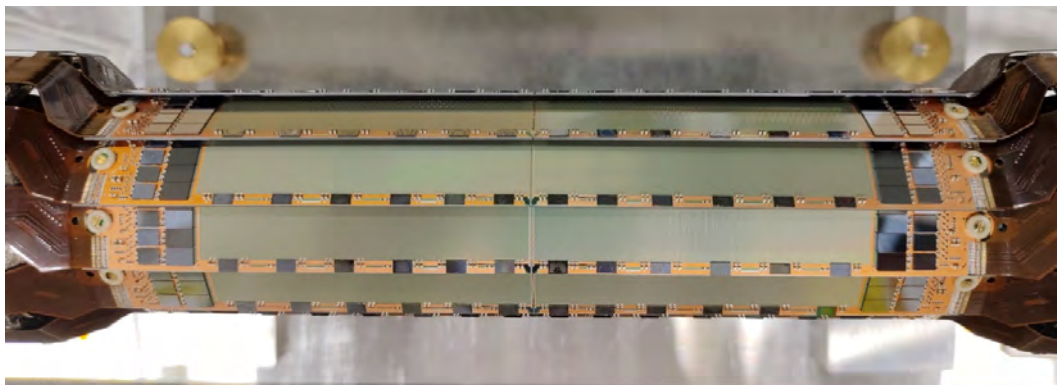
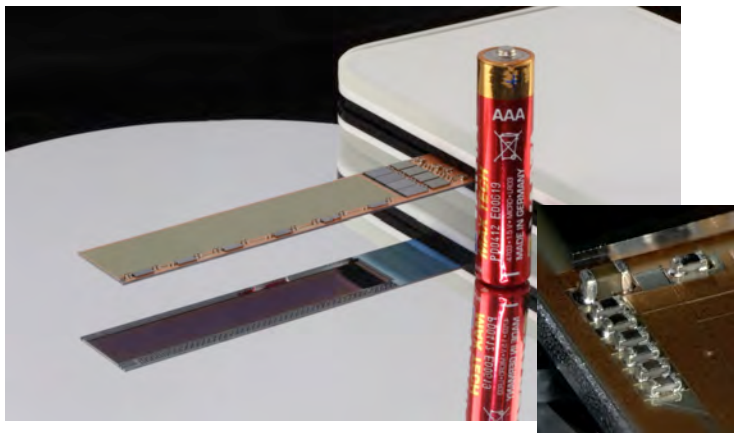


Sensor **2.56 x 10.24 cm²**
 512 x 128 pixels
 Hybrid detector
 with 8 readout ASICs (64x64)
 Pixel size: 204 x 236 μ m²
 Frame time: **220ns (4.5MHz)**



● BELLE II @ SuperKEKB

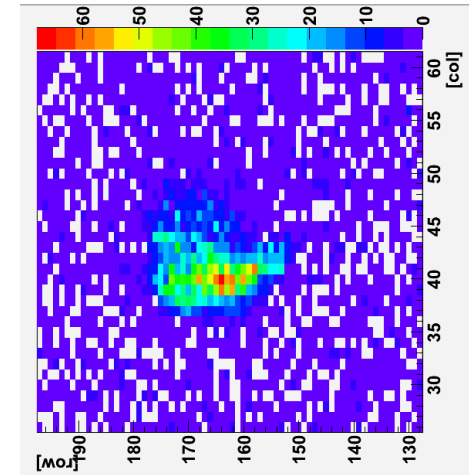
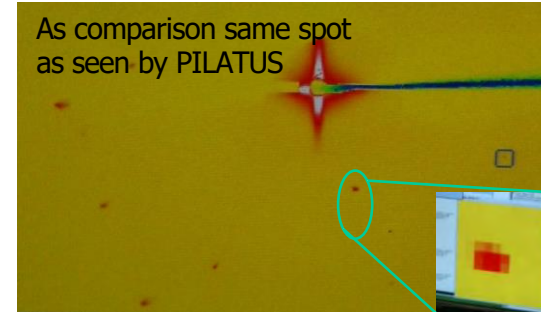
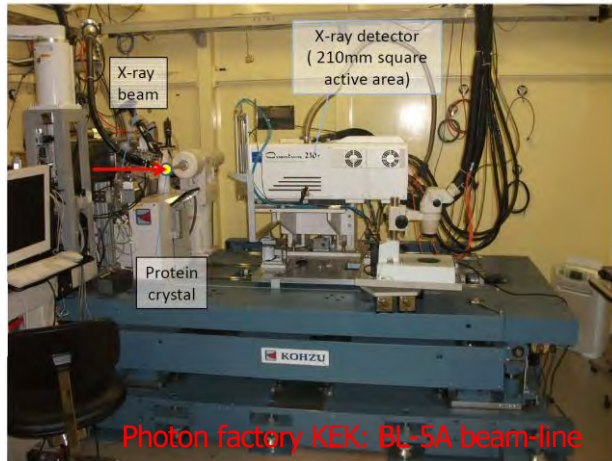
In Japan



● BELLE & ILC DEPFETs for Photon Science

First tests: slow readout system 2.3ms frame readout time (signal integration time) with about 150Hz DAQ readout rate (one frame is read out every 6ms)

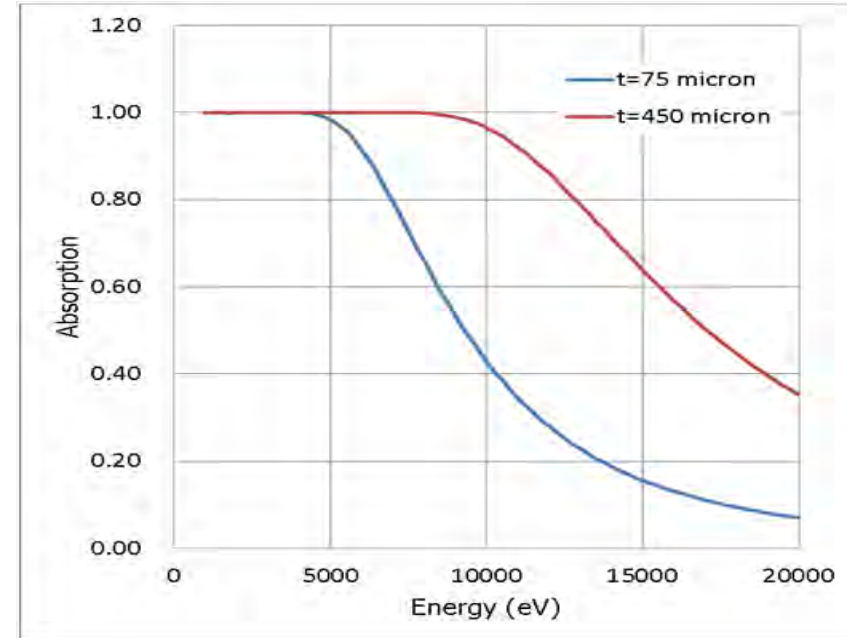
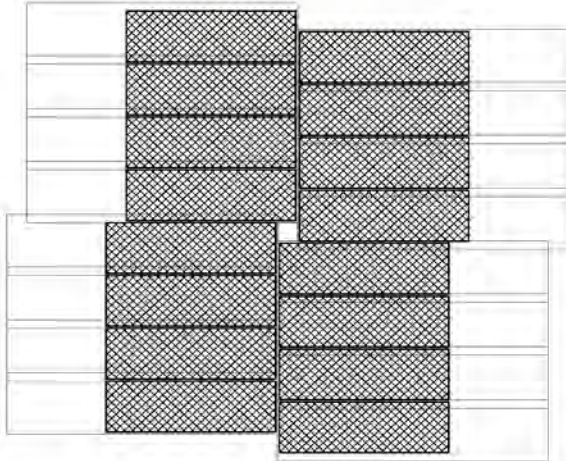
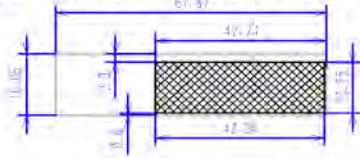
Matrix – ILC type 24x32 μm^2 pixel 450 μm thick
5120 μm x 1280 μm (256 x 64 pixels)



Lysozyme crystal – position of diffraction spots defined by PILATUS and then DEPFET matrix driven to that point

- BELLE like sensors (20 μ s) for PF KEK

pixel size: 55 μ m x 55 μ m
number of rows and columns: 250 x 768



ATHENA mission

■ ESA mission

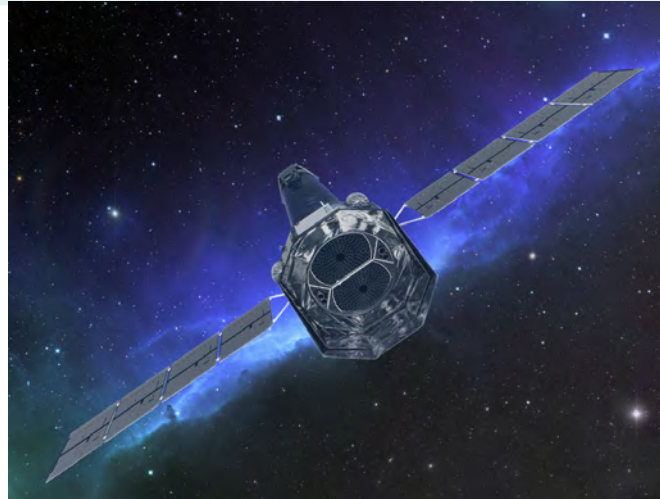
- large X-ray observatory

■ science targets

- theme 'The Hot & Energetic Universe'
 - formation of large scale structures
 - evolution of black holes

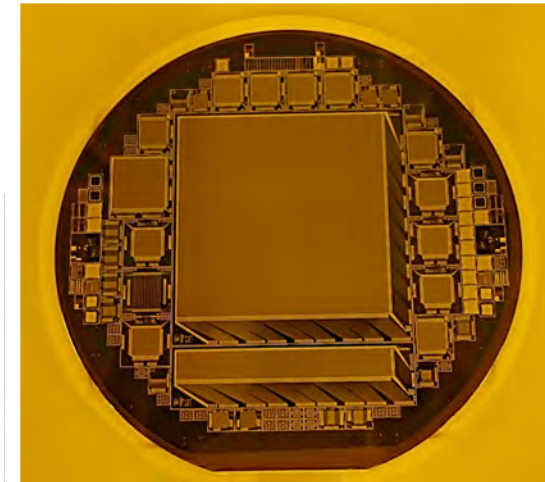
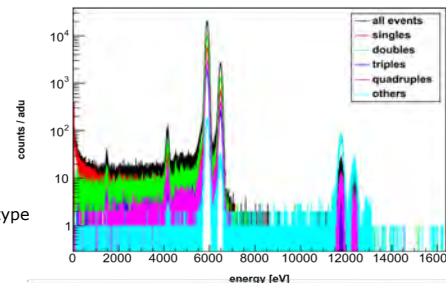
■ scenario

- launch > 2035
- Ariane 5 carrier
- halo orbit around Lagrange point L2
- design life time 5 y (+5 y)
- 300 observations per year



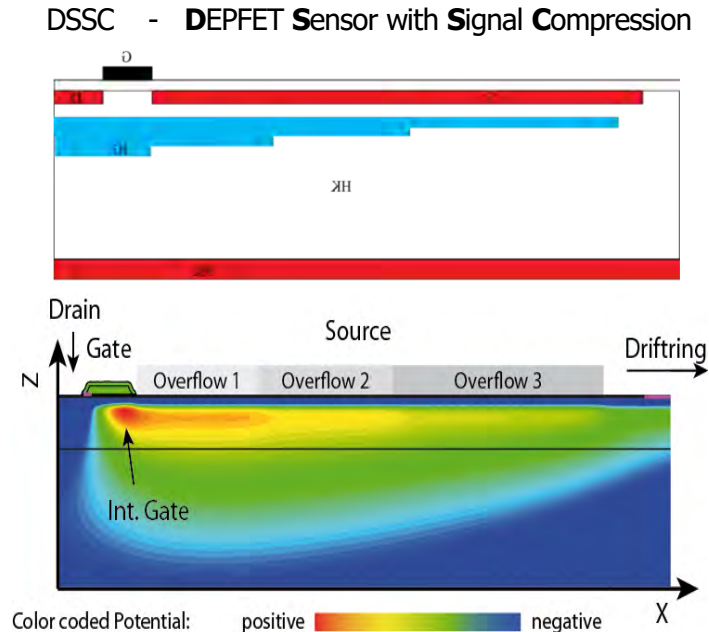
Sensor: 512 x 512 pixels
78.00 x 76.15 mm²
rolling shutter mode
Pixel size: 130x 130 μm^2
Frame time: **1.28 msec, i.e. 2.5 μsec / row**
with 128 eV (singles) & 136 eV (all)

energy spectrum of a ^{55}Fe source
recorded with a WFI prototype
(64 x 64 pixels)



● Detector Concept – DEPFET with signal compression

Motivation: develop detector with high dynamic range and preserve other advantages of DEPFETs



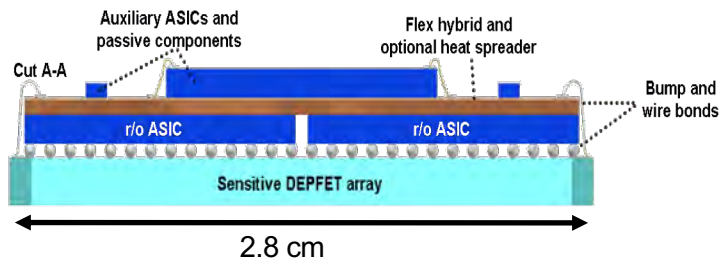
- The internal gate extends into the region below the source
- Small signals assemble below the channel, being fully effective in steering the transistor current
- Large signals spill over into the region below the source. They are less effective in steering the transistor current.
- 200 x 200 μm pixel has been designed and produced
- 60 x 60 μm pixel has been designed and is being produced now

● Requirements for the XFEL detectors

Integrating Area Detector

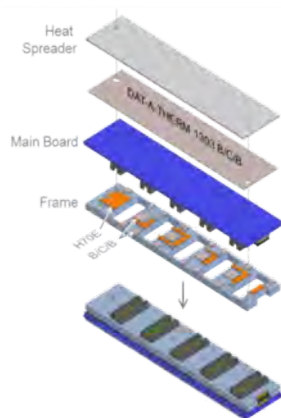
	XFEL (e.g. XPCS)	DEPFET array system
single photon resolution	yes	yes
energy range	$0.5 < E < 24$ (keV)	$0.5 < E < 25$ [keV]
ang. resolution or pixel size	4 μ rad	200 μ m
sig.rate/pixel/bunch	10^3	10^3 @10KeV
quantum efficiency	> 0.8	> 0.8 from 0.3 to 12 keV
number of pixels	512 x 512 (min.)	1024 x 1024
frame rate/repetition rate	10 Hz	yes, triggerable
XFEL burst mode	5 MHz (3.000 bunches)	4.5 MHz
Readout noise	$< 150 e^-$ (rms)	$< 50 e^-$ (rms)
cooling	possible	- 20° C optimum, room temperature possible
vacuum compatibility	yes	yes
preprocessing	no (yes) ?	possible upon request
4-side buttability	yes	yes

Submodule 128x512

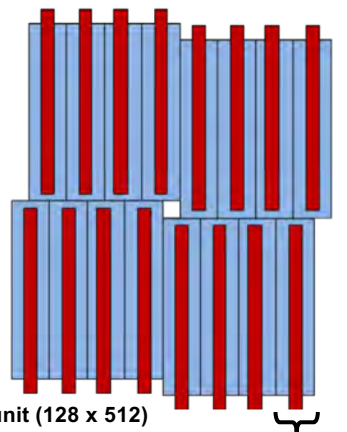


Multi Chip Modules

- ▷ DEPFET Sensor bump bonded to Readout ASICs
- ▷ Optional Heat spreader
- ▷ Flex Hybrid with passive components and auxiliary ASICs (e.g. voltage regulators)
- ▷ Sensor (512x128 pixels)
2.56x10.24 cm²
- ▷ 16 readout ASICs (64x64)
- ▷ Dead area: 10-15%



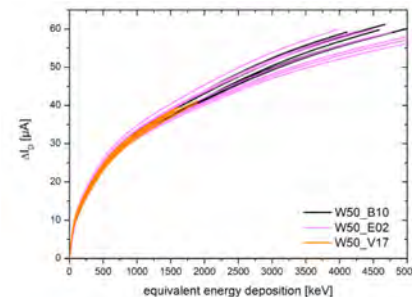
21 cm



Monolithic detector subunit (128 x 512)

Sensor development by MPG HLL
System development by DSSC collaboration

Fully functional devices delivered in early 2015

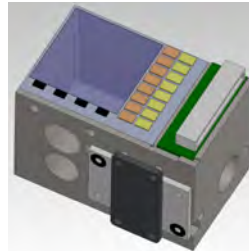
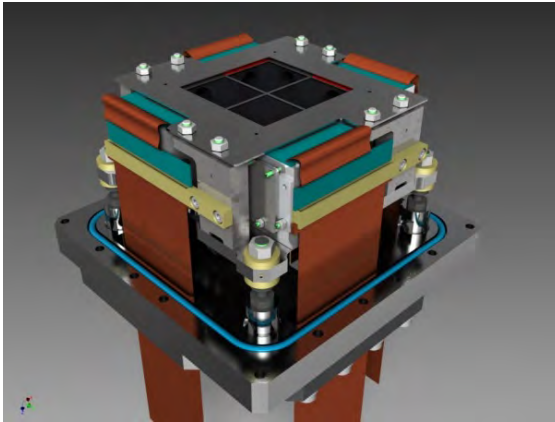
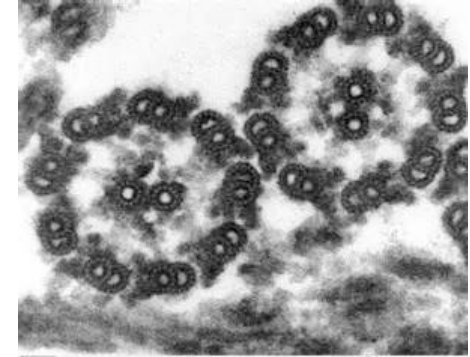


● DEPFETs for low E electron detectors

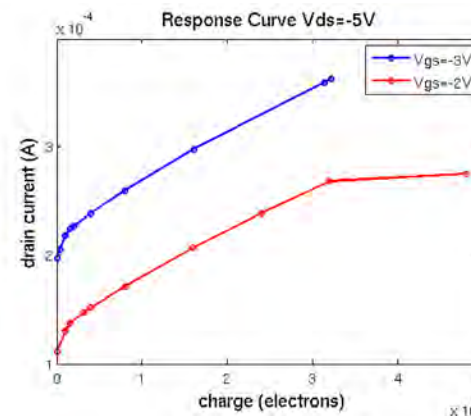
Goal: develop high speed direct hit low energy electron detector

Solution: thin, nonlinear DEPFETs with 80kHz frame rate

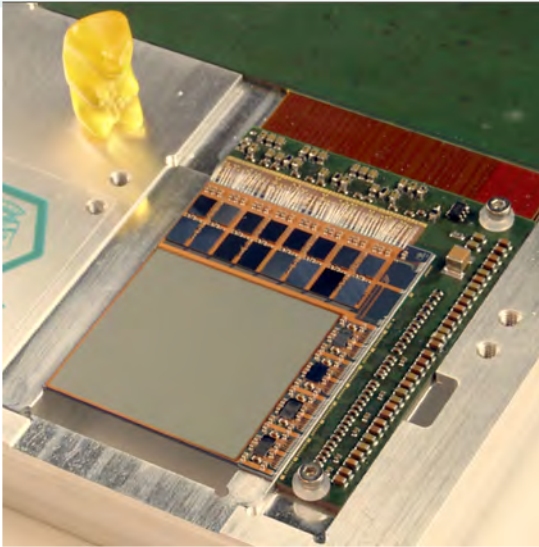
- 1Mpix, 60 μm DEPFET pixel, 4 quadrants, 6x6 cm² sensitive
- 1-3 M electrons to store into internal gate
- 30-50 μm thin sensitive area
- Bidirectional 4-fold read out, frame rate: 80kHz
- memory to store ~ 60 frames



(collaboration partner MP Structural Dynamics)

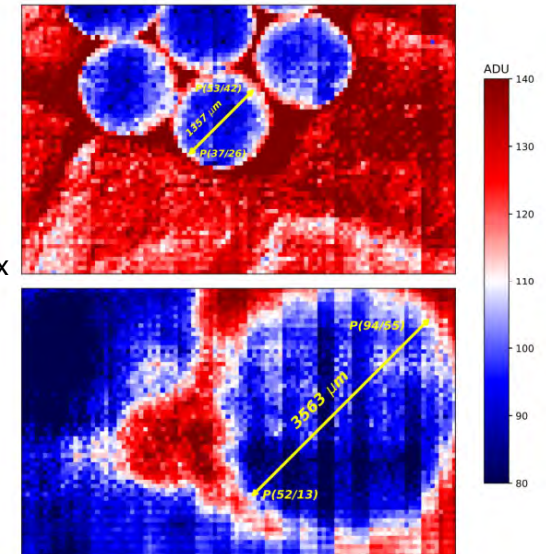
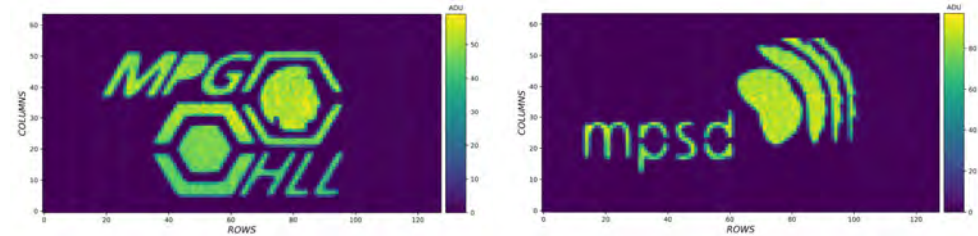


- DEPFETs for low E electron detectors



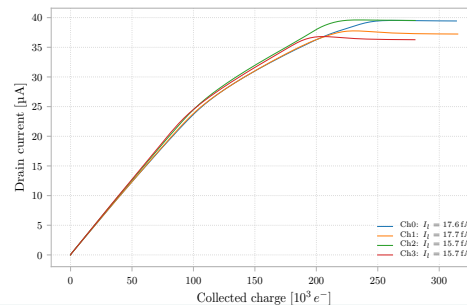
Edet 80k assemblies (30-50 μ m thin sensors)

Tests with small format prototype devices



Images of 261 nm latex spheres for calibration purposes

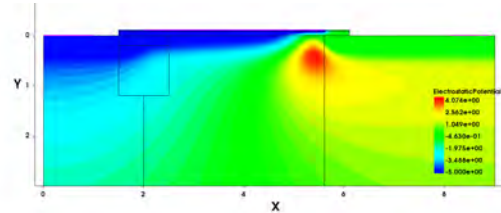
First measurements on the non linear characteristics



● DEPFETs – advanced concepts

Super g_q DEPFETs – Super high S/N

- New DEPFET technology allows **improved S/N** of a factor of 3
- better S/N \rightarrow better spectroscopic applications (**ENC > 1e-**)
- **High speed** readout devices
- **High precision** devices
- **High dynamic range** DEPFETs
- thinner detectors
- Smaller bias current - **less power** in pixel area
- Thinner gate isolator - **higher radiation** tolerance

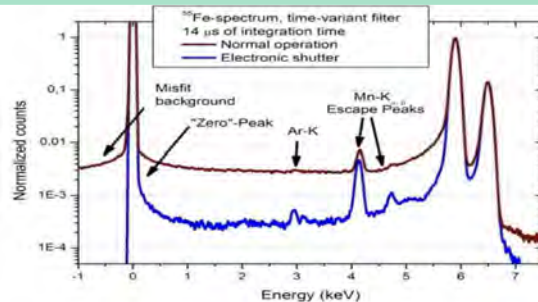


Combine different
conceptual
features

Create devices
with multiple
capabilities

Gated DEPFETs - precise timing

- allows replacement of external shutters \rightarrow better timing properties
- Sensors for experiments requiring **selective sensitivity**, e.g. light curve measurements, LIDAR, AO etc.

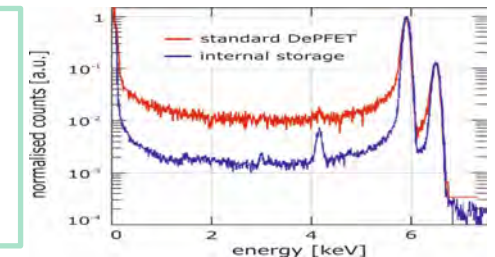
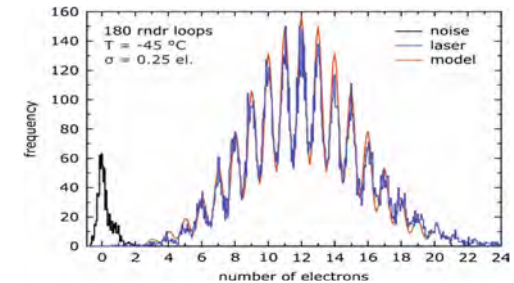


Multiple DEPFET structure – NO deadtime

- superpixel is composed of two or more standard or advanced DEPFET subpixels, which are alternately used for the detection of charge.
- one subpixel is read out, while the other one is collecting new charge

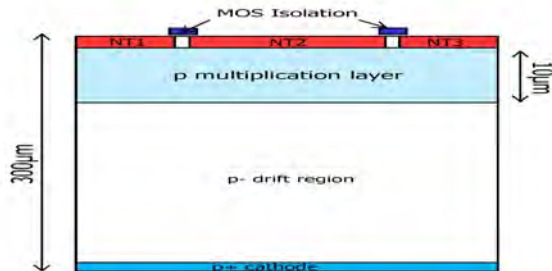
Repetitive readout – sub e^- resolution RNRD DEPFETs

- an equivalent noise of 0.2 e^- is achieved in ~ 6 ms with 180 transfers
- **Extremely low noise** and background suppression
- Experiments w/ single electron sensitivity (e.g. low light level astronomy)
- Extremely low background applications (e.g. dark matter detection)

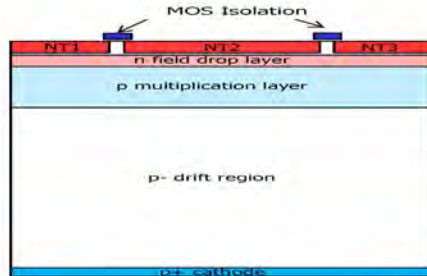


● MARTHA - Monolytic Array of Reach Through APDs

Initial motivation – develop low gain avalanche device with high fill factor for photon science applications

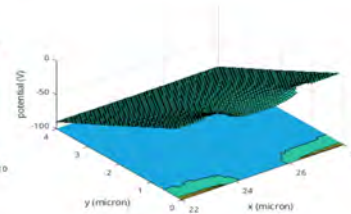
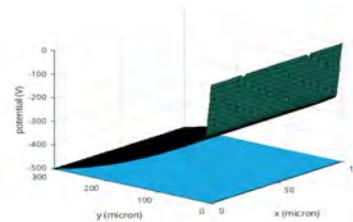


HF region
extends over
pixel gaps

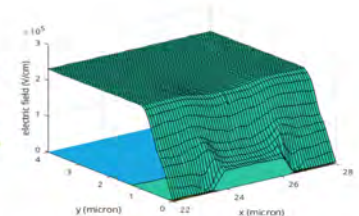
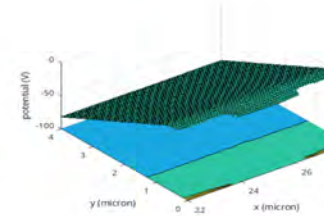
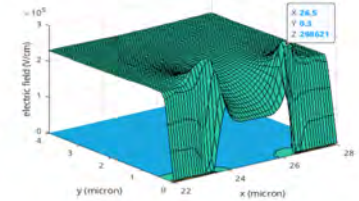


HF region and
field drop layer
extend over
pixel gaps

Potentials



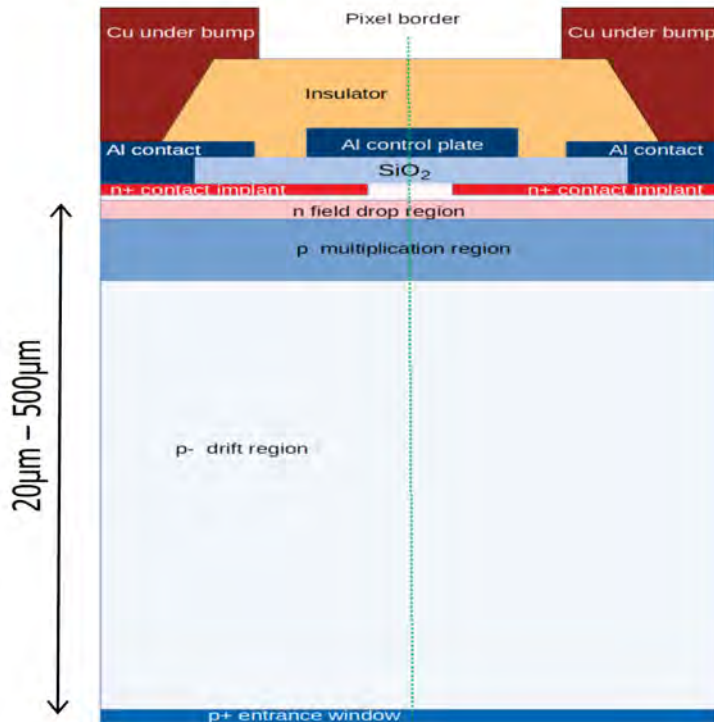
E Field



$V_{MOS}=3V$

● MARTHA - **M**onolytic **A**rray of **R**each **T**hrough **A**PDs

Initial motivation – develop low gain avalanche device with high fill factor for photon science applications



Expected features:

Gain up to 20

Collection efficiencies: > 99%

Pixel pitch: given by bump bond technology
and read out electronics space consumption (ATLAS 50μm)

Position resolution: $< < \frac{pitch}{\sqrt{12}}$ ($< < 10\mu m$)

Time resolution:

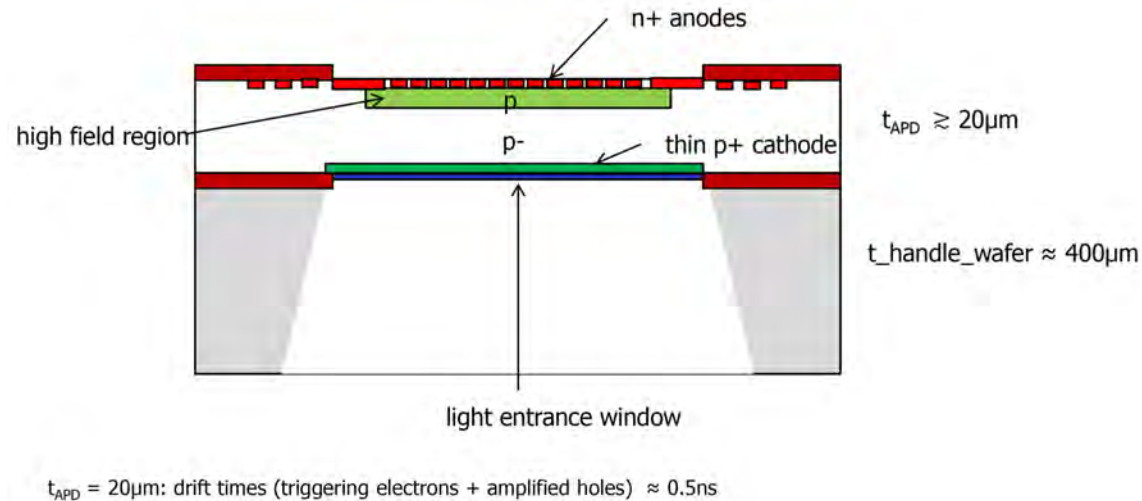
Application dependent

Leading edge trigger: <50ps

Full signal formation 50ns (for thickness 500μm)

- MARTHA - **M**onolytic **A**rray of **R**each **T**hrough **A**PDs

Faster device for particle tracking ? → Thinned Reach Through APD based on HLL SOI Technology



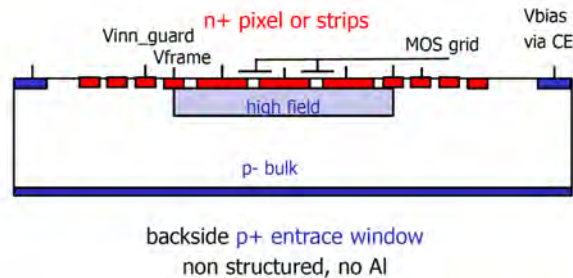
Full signal formation 0.5ns (50ns for thickness 500 μm)

● MARTHA - **M**onolytic **A**rray of **R**each **T**hrough **A**PDs

Proof of principle production ongoing on standard thick material

Aims

- proof of concept
- Efficiency, gain, cross talk and noise studies (vs T)
- find a reliable narrow guard ring structure (in view of high voltage operation, buttable arrays)



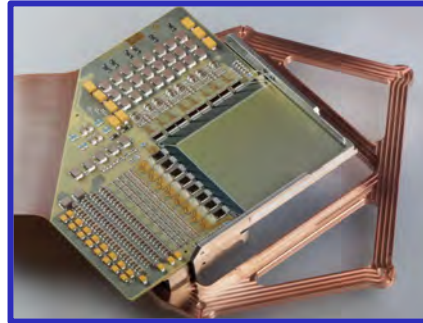
Designed structures:

- Pixel arrays
- Strip sensors
- Diodes
- Multi Guard Ring Test diodes

● Interconnection technologies

Standard wire bonding (Al and Au)

Frame time: 1.28 msec,
i.e. 2.5 μ sec / row



Athena WFI module

Courtesy MPE

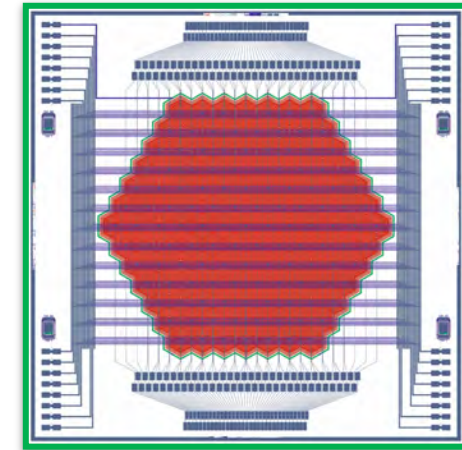
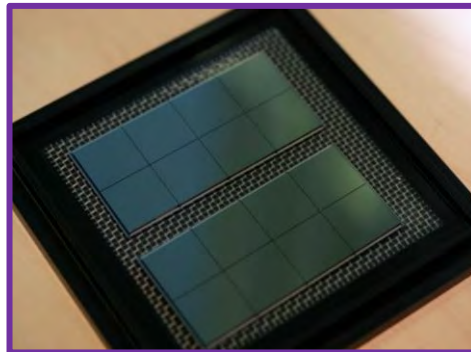
Full parallel readout

dedicated wire routing

flip chip technology – hybrid detectors



DSSC module
With 8 CMOS chips
Frame rate: 4.5MHz



Full frame read-out DePFET detector

application **ultra-fast X-ray timing & imaging**
frame rate > 100 kHz

sensor 127 hexagonal hexagonal pixels
cell diameter 800 μ m

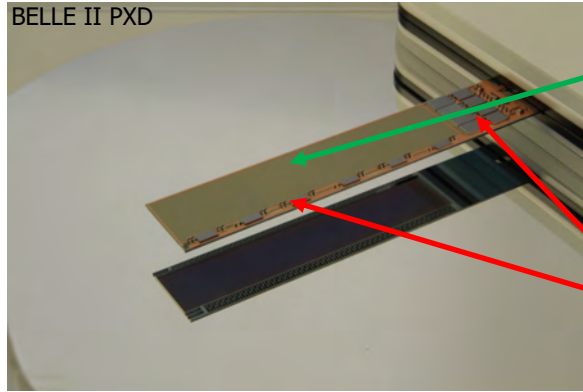
DePFET with internal storage

● Interconnection technologies – All Silicon Module (ASM)

Sensor and Hybrid in one silicon piece

- Belle II Pixel detector – tracking of high energy particles
- EDET80k project – development of ultra fast direct electron detectors for TEM

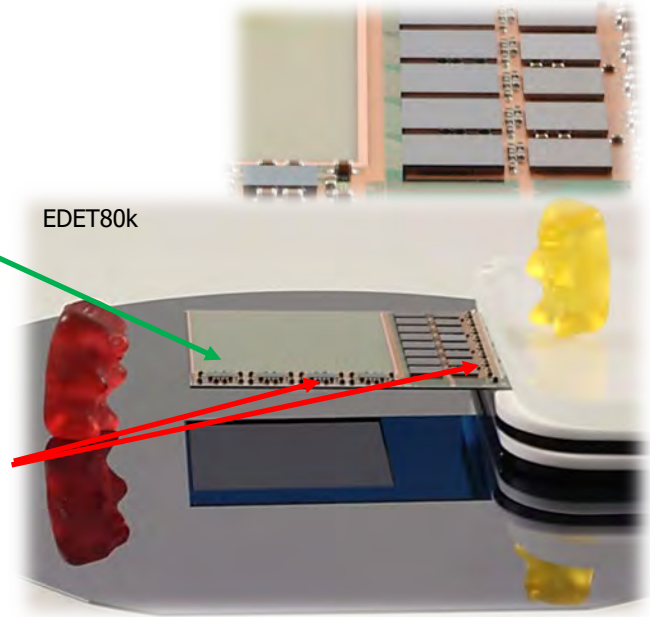
BELLE II PXD



Thin sensitive area with
nonlinear DEPFETs

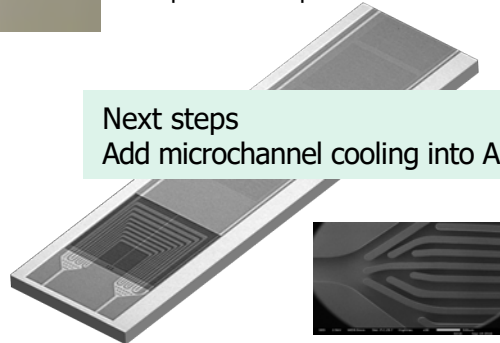
Thick silicon area for cooling and
landing pads and interconnection for the
read out and steering electronics and all
passive components.

EDET80k



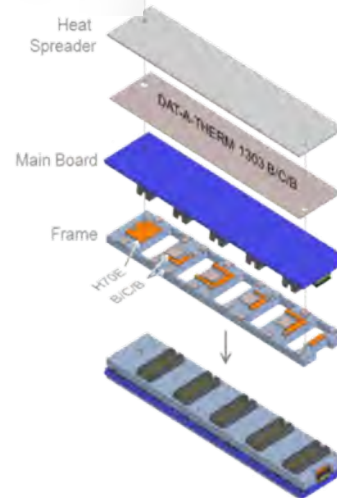
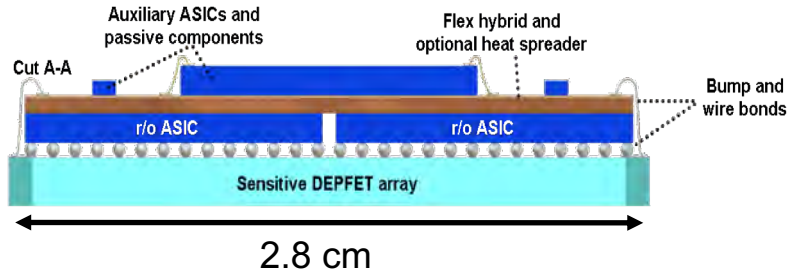
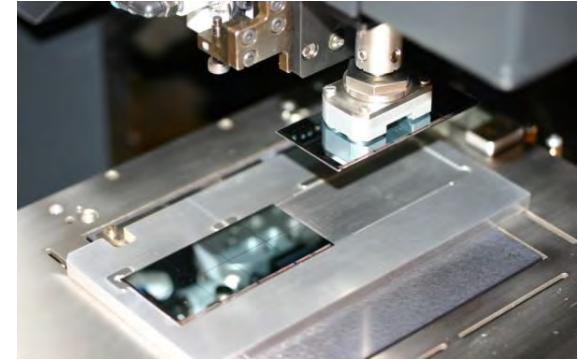
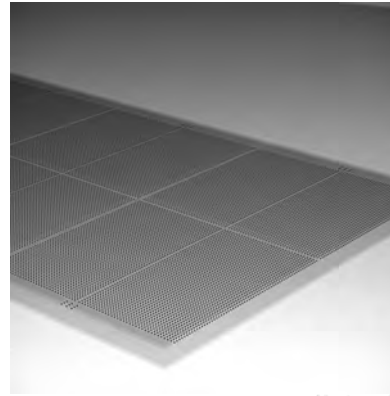
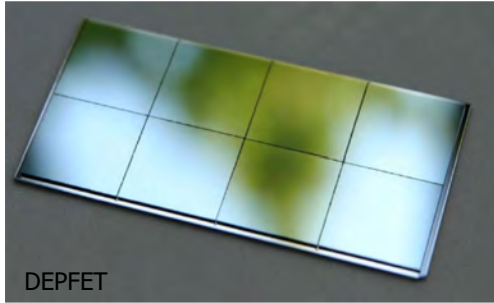
~50 μ m pixel size
8M pixel detector
50kHz frame time
75 μ m thin detectors
Linear DEPFETs

Next steps
Add microchannel cooling into ASM

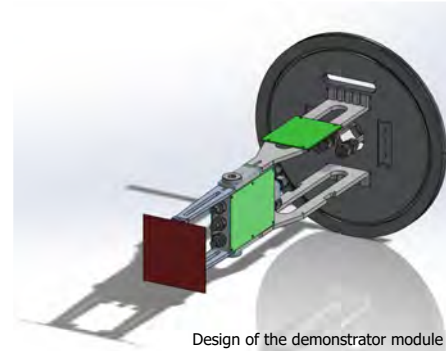
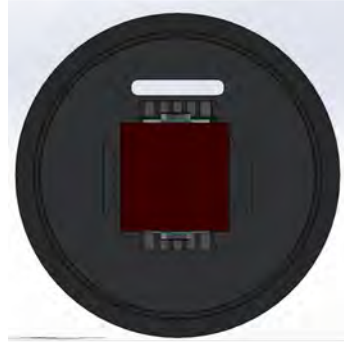
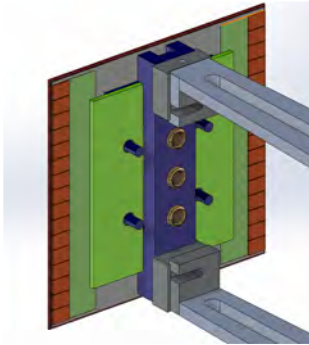


60 μ m pixel size
1M pixel camera
80kHz frame time
30 and 50 μ m thin detectors
Nonlinear DEPFETs

● Macro/Micro assemblies



● 4 side buttable module development @ HLL



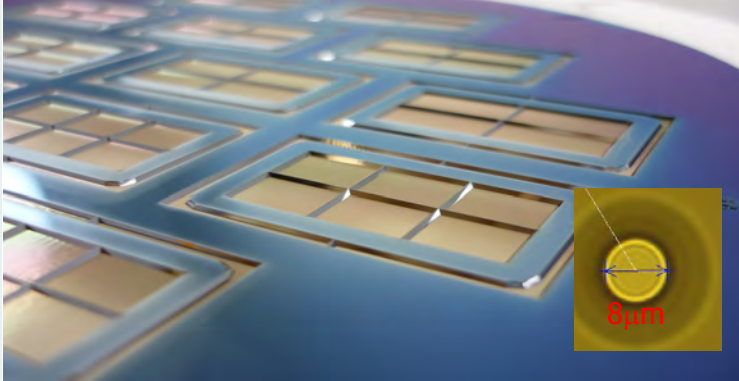
Design of the demonstrator module

TrueTile:

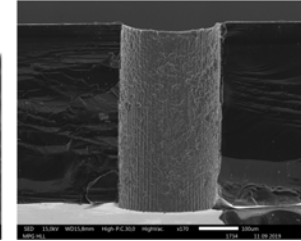
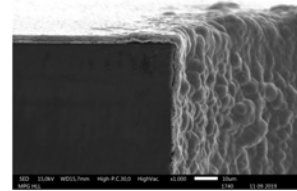
- **Novel concept** for sensor integration
- **Compact and modular** for high-density sensor integration
- **4-side buttable** devices - large sensor areas with extremely low sensitivity gaps
- Core element: **Active cooling interposer (AI)** for frontend supply integration and cooling
- Multi-level development project
- Large area pnCCD as demonstrator device
 - 1 MPixel with $75 \times 75 \text{ mm}^2$ pixels, $76.8 \times 76.8 \text{ mm}^2$
- Interposer with microchannel cooling structures
- Compact camera interior for standalone operation

- Non active components

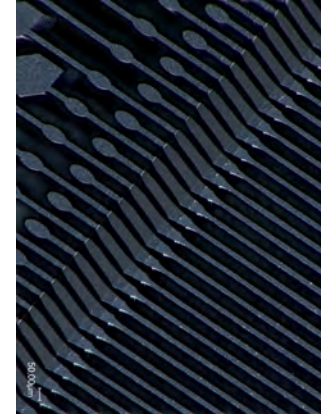
Production of perforated thin membranes as sample holders



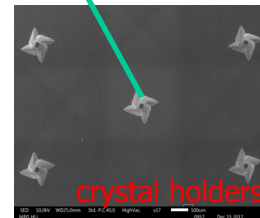
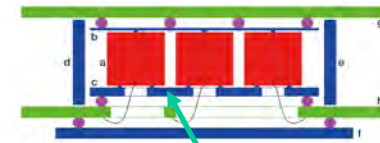
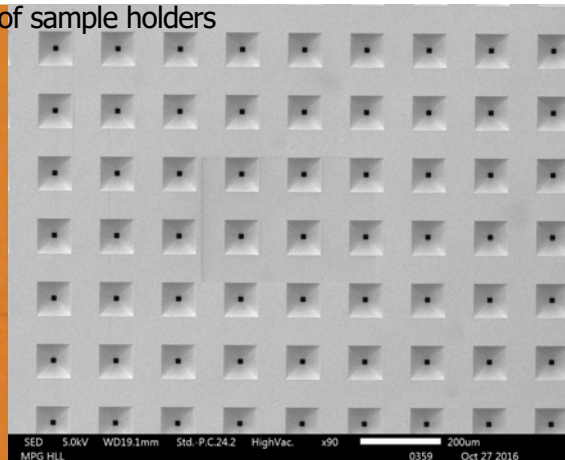
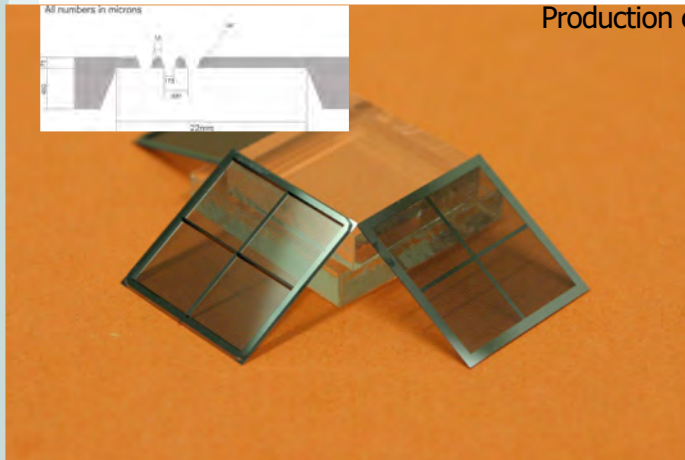
Trough silicon vias



Metallization over
extreme
topography

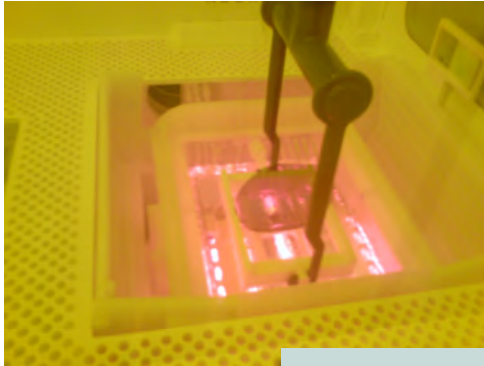


Production of sample holders

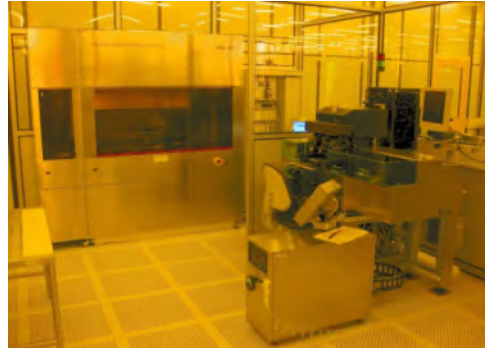


● Inside HLL

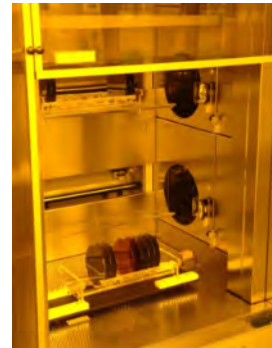
cleaning



lithography



thermal



inspection



implantation



6" Si full processing line
class 1000 (ISO5) to class 1 (ISO3) in certain areas



plasma and sputter



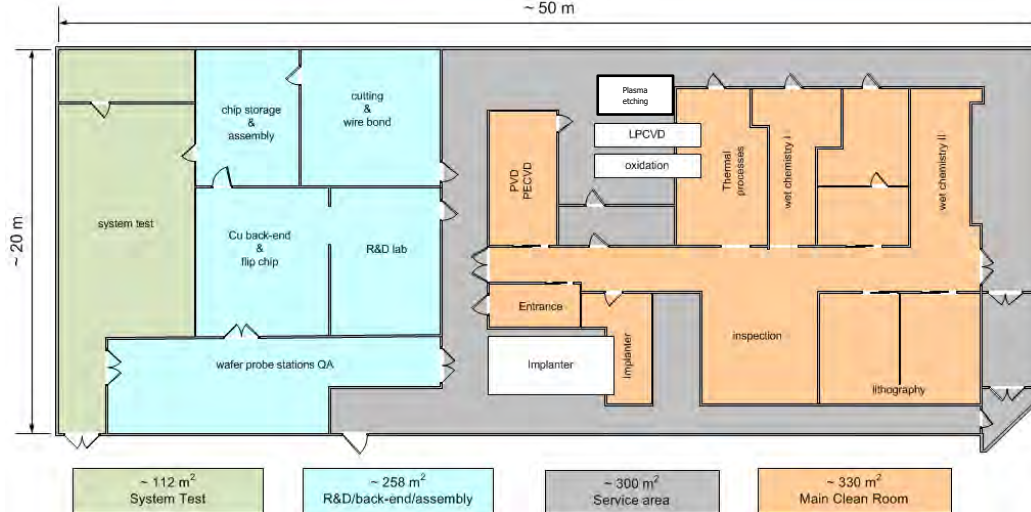
Cu line



flip chip



assembly and test



● New MPG HLL building

MAX PLANCK
SEMICONDUCTOR
LABORATORY



■ ■ ■ CARPUS+PARTNER



● Building description



- New HLL building on IPP campus Garching
- Building divided into two parts: laboratory with technical areas / academic offices
- Arrangement of the two structures creates entrance area in the west



Front view



Rear view

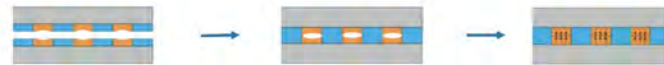
- Impressions from the site 12/2022



● Munich Quantum Valley @ MPG HLL

- Post processing of CMOS and PIC wafers
- Wafer-wafer and wafer-chip bonding
- Interconnection and assembly

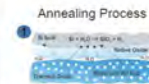
Fusion / Hybrid Bonding | Mechanisms and Process Flow



Wet cleaning and plasma activation are applicable for surface preparation.

Wet cleaning can include the use of chemicals for metal oxide removal.

Wafers will be aligned using F2F optical alignment. Once aligned, wafers will be contacted at room temperature.

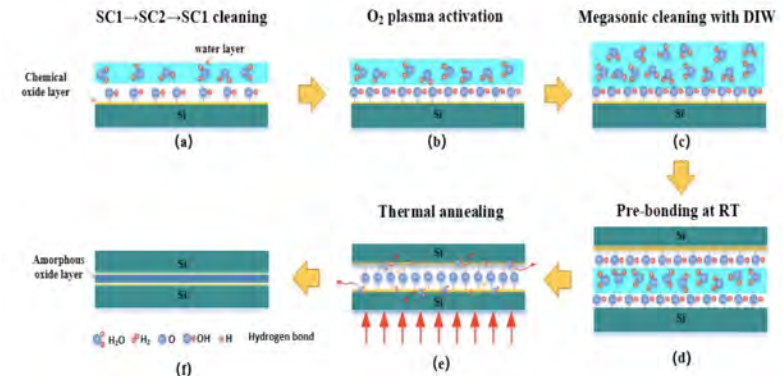
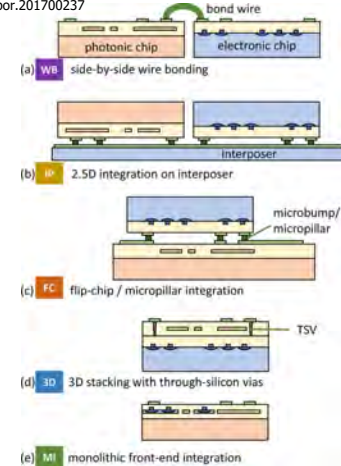


Dielectric layer Annealing



Interconnect gap closure due to different CTE of Dielectric bonding material and interconnect material

<https://doi.org/10.1002/lpor.201700237>



<https://doi.org/10.3390/pr9091599>

Hamburg, 30th June 2023

Thank you for your attention ...



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